

**CLAIMS**

1. A cleaning method for cleaning at least part of an  
ultrapure water supply system having an ultrapure water  
production apparatus connected to a point of use of  
5 ultrapure water via a passage, comprising the steps of:

(a) changing surface potential of fine particles  
present in the at least part of the ultrapure water supply  
system; and

(b) discharging the fine particles from the at least  
10 part of the ultrapure water supply system to outside.

2. The cleaning method according to claim 1, wherein  
in said step (a), the fine particles are made to contact  
with a basic solution or a solution of surfactant.

3. The cleaning method according to claim 1, wherein  
15 in said step (a), the surface potential of the fine  
particles is changed and also physical force is applied to  
the fine particles.

4. The cleaning method according to claim 3, wherein  
in said step (a), a basic solution or a solution of  
20 surfactant is caused to flow through the at least part of  
the ultrapure water supply system at a flow velocity of  
0.5 m/sec to 2.0 m/sec.

5. The cleaning method according to claim 3, wherein  
in said step (a), with a basic solution or a solution of  
25 surfactant kept in contact with the at least part of the  
ultrapure water supply system, the solution is applied with  
small-amplitude vibration.

6. The cleaning method according to any one of claims  
2, 4 and 5, wherein the basic solution is an aqueous  
30 solution of ammonia or ammonium salt, or an aqueous  
solution of alkali metal hydroxide, or a mixture of the  
aqueous solution of ammonia or ammonium salt and the  
aqueous solution of alkali metal hydroxide.

7. The cleaning method according to any one of claims 2, 4 and 5, wherein the basic solution is pure water or ultrapure water in which alkaline gas is dissolved.